

Fig. 1 (prior art)

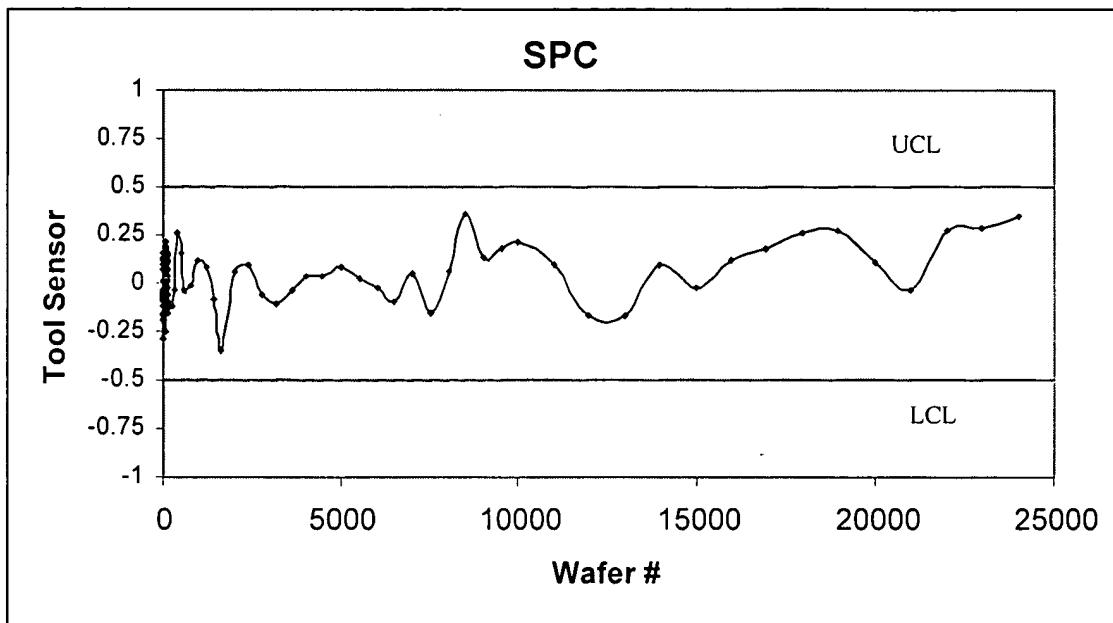


Fig. 2 (prior art)

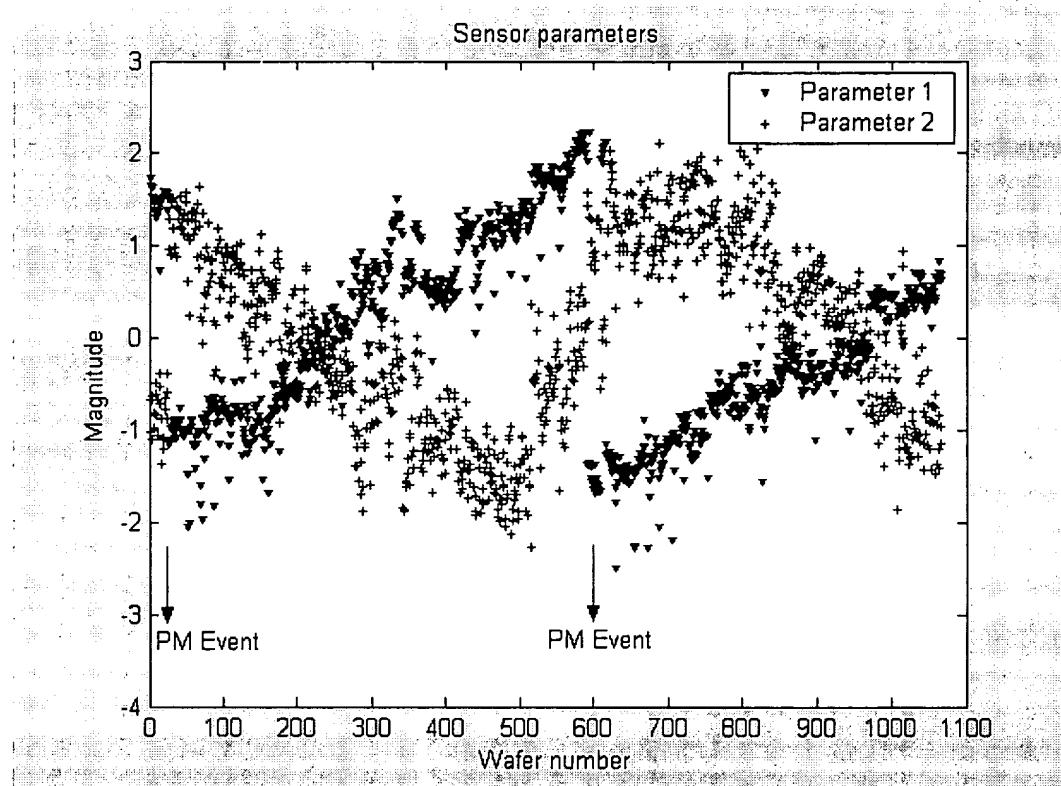


Fig. 3 (prior art)

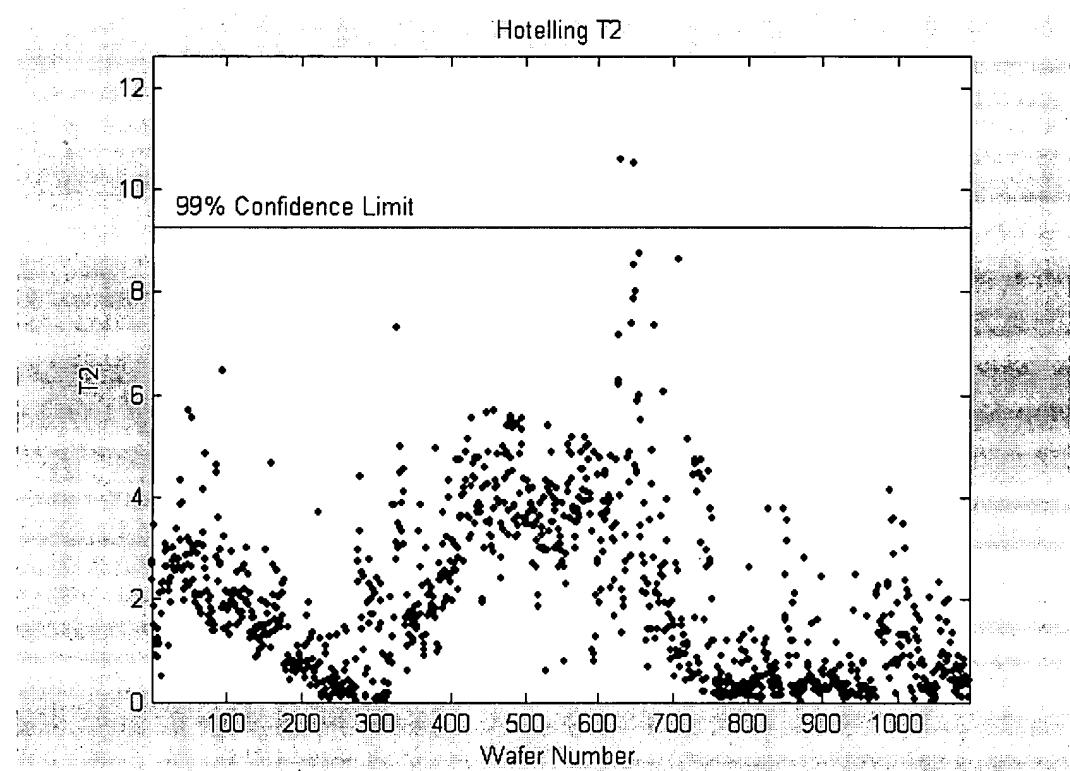


Fig. 4 (prior art)

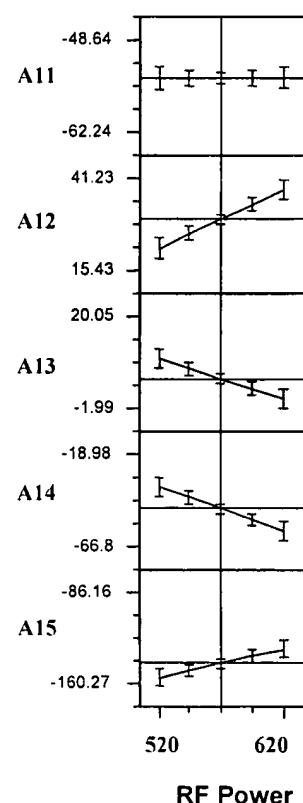
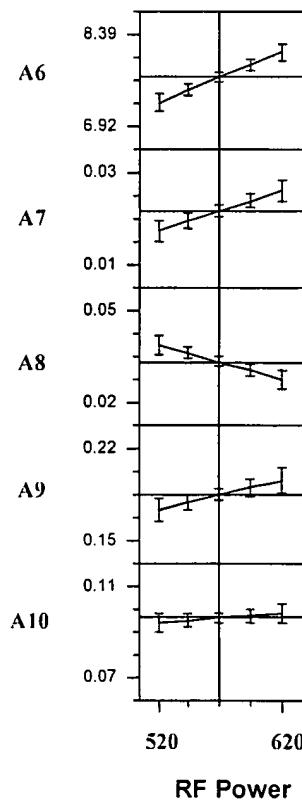
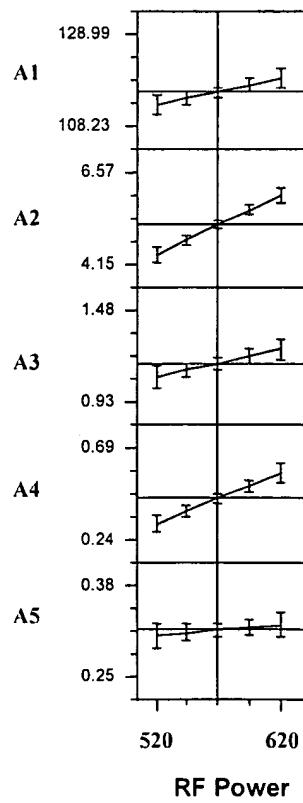
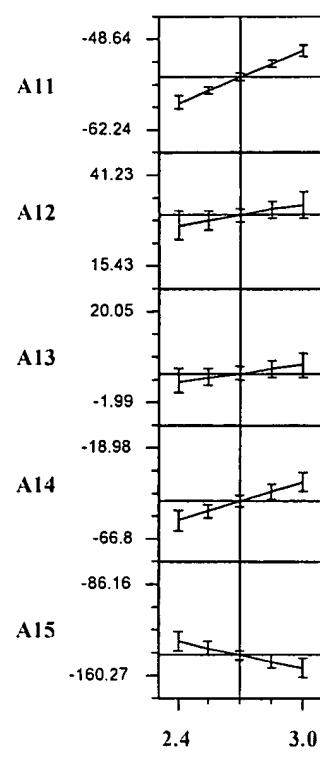
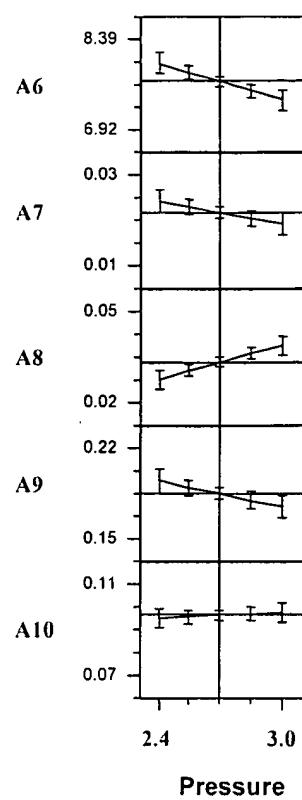
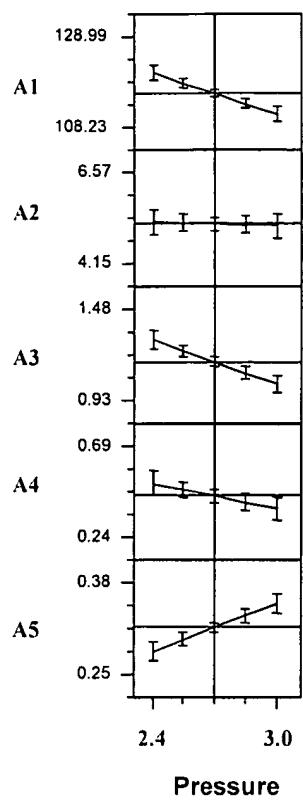


Fig. 5

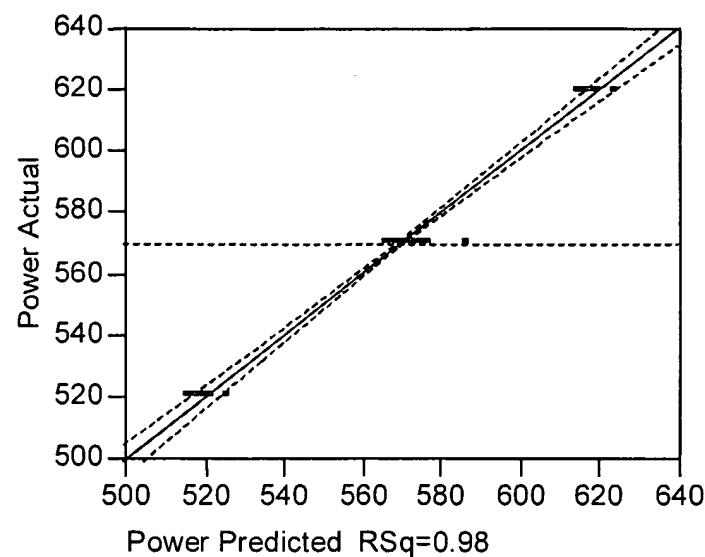


Fig. 6

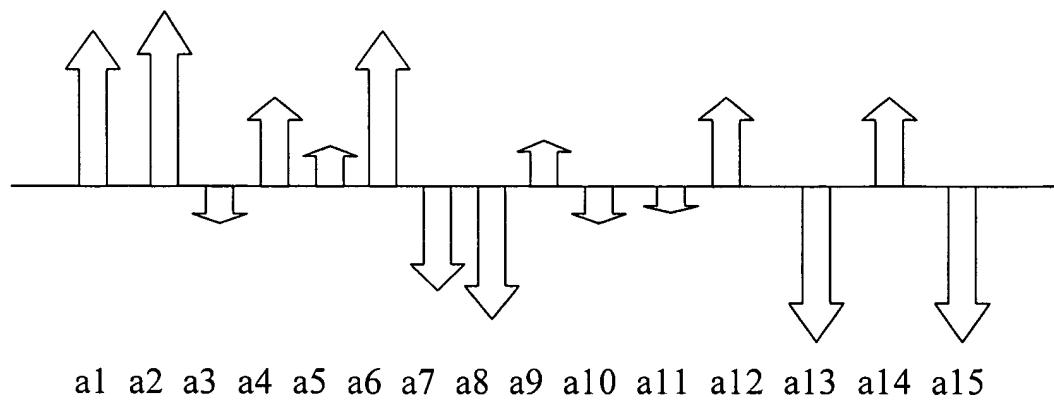


Fig. 7

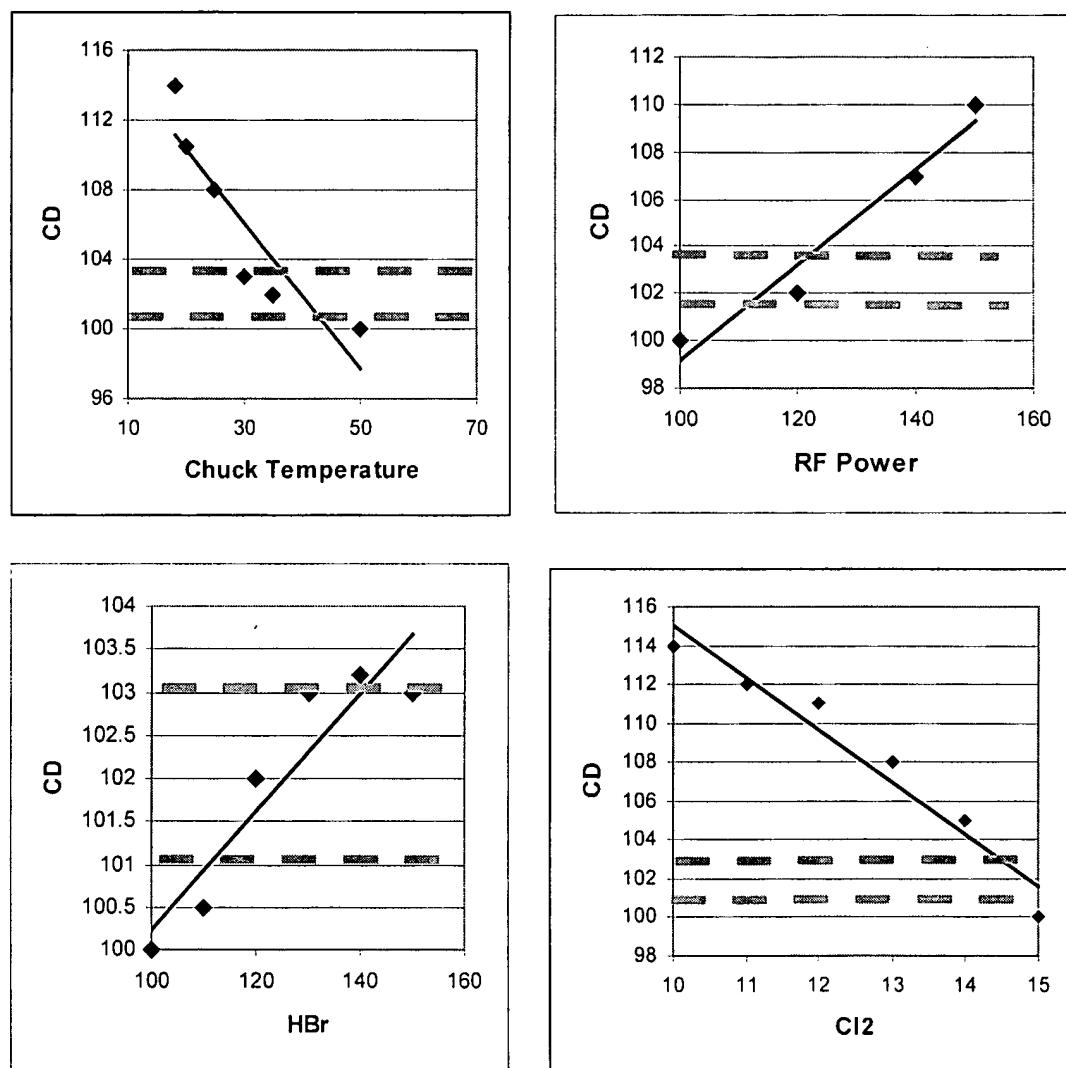


Fig. 8

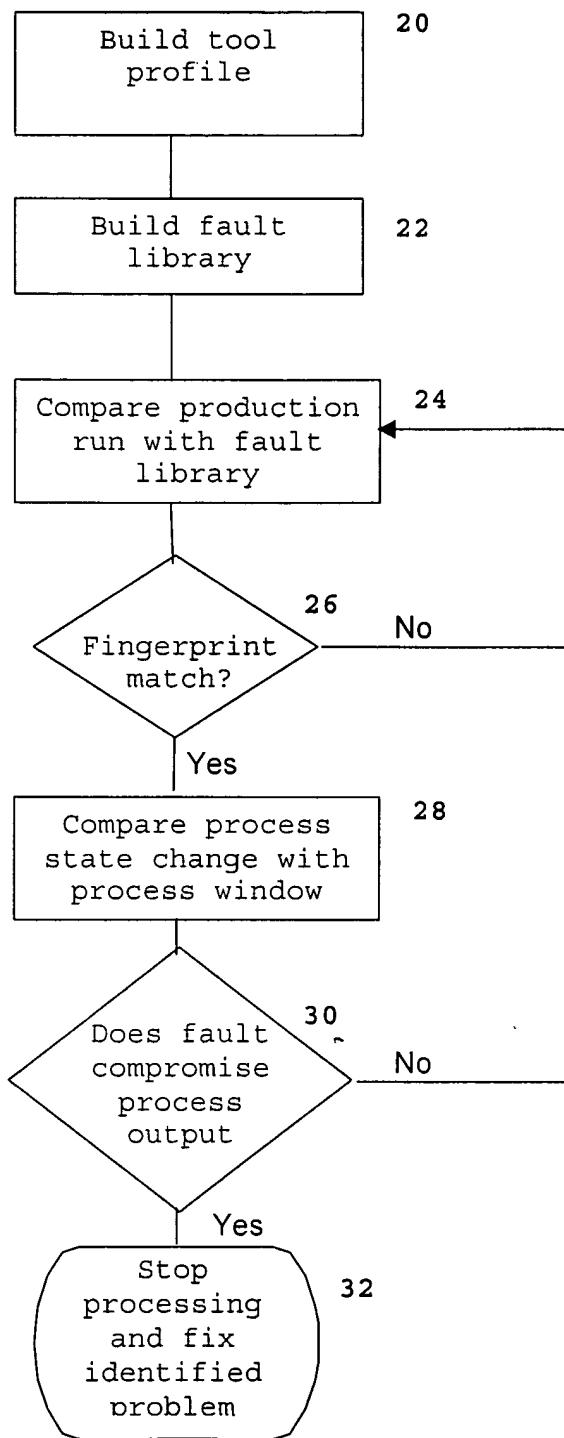
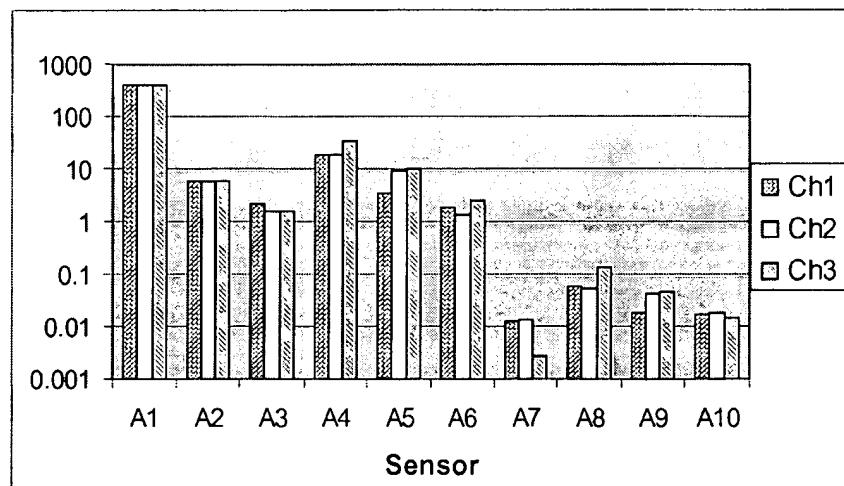
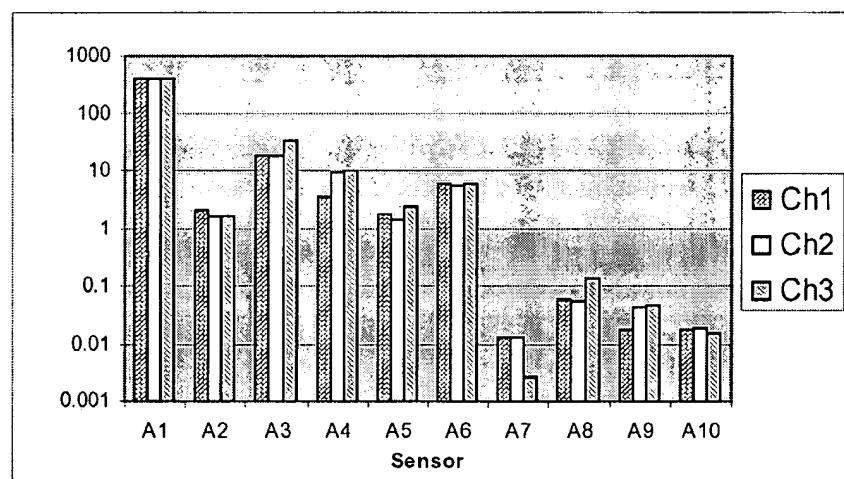


Fig. 9



(A)



(B)

Fig. 10

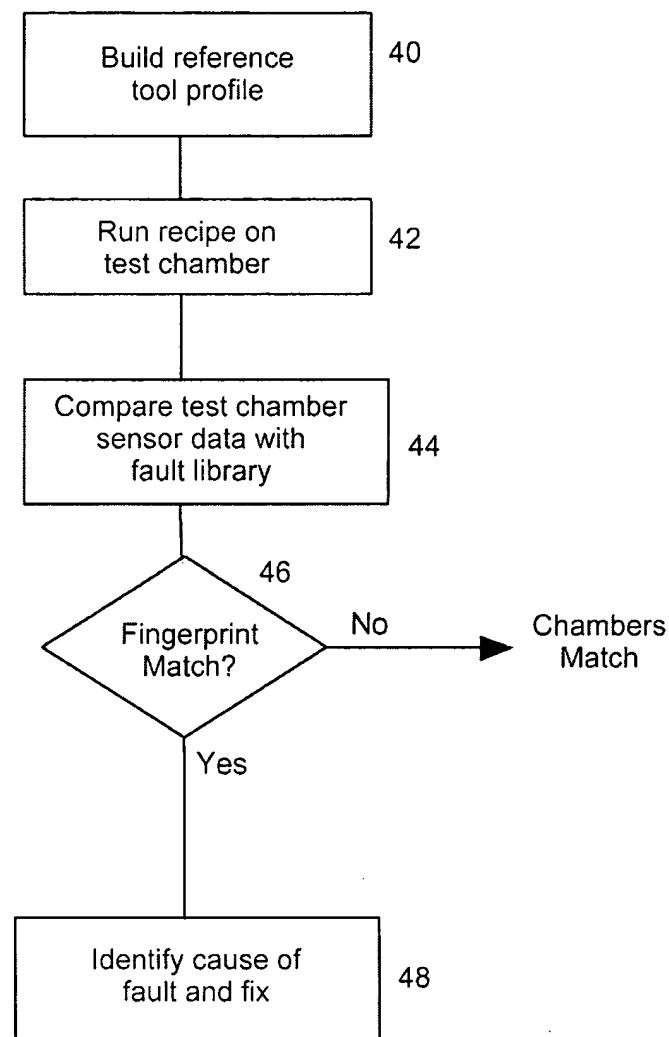
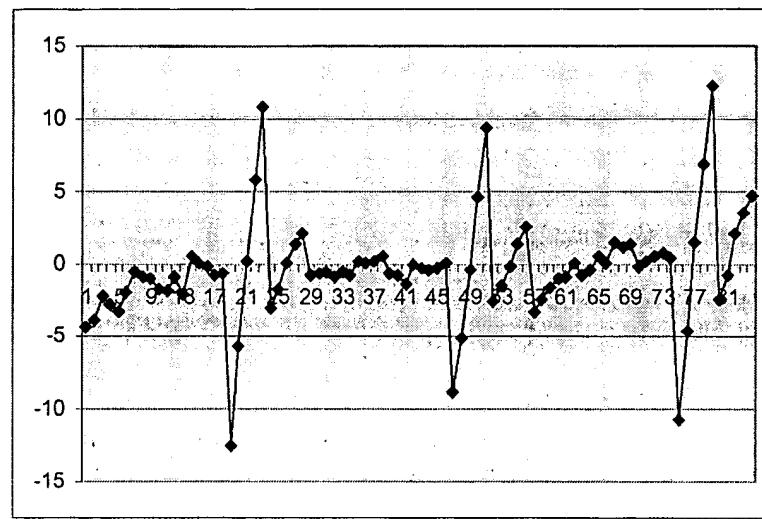
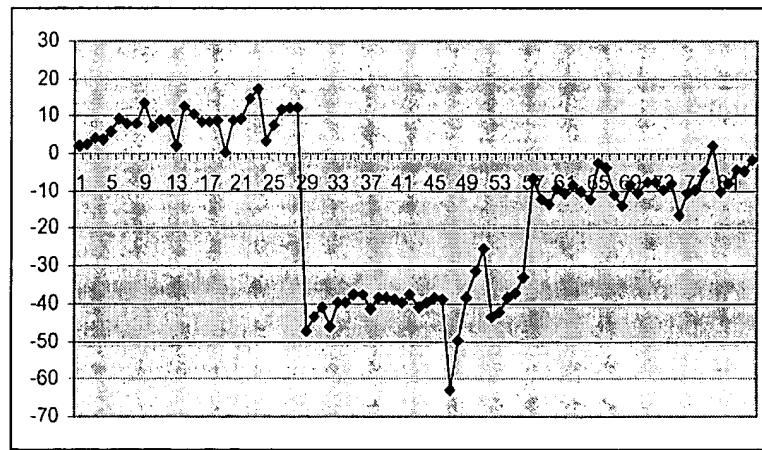


Fig. 11



(A)



(B)

Fig. 12

Wafer Number	Forced Change	Change Direction
1	Argon	-
2	Argon	Nominal
3	Argon	+
4	C5F8	-
5	C5F8	-
6	C5F8	Nominal
7	C5F8	+
8	C5F8	+
9	Gap	-
10	Gap	-
11	Gap	Nominal
12	Gap	+
13	Gap	+
14	Oxygen	-
15	Oxygen	-
16	Oxygen	Nominal
17	Oxygen	+
18	Oxygen	+
19	Power	-
20	Power	-
21	Power	Nominal
22	Power	+
23	Power	+
24	Pressure	-
25	Pressure	-
26	Pressure	Nominal
27	Pressure	+
28	Pressure	+

Fig. 13